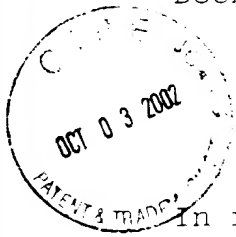


PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Tuqiang NI et al

Serial No. 09/689,616

Filed: October 13, 2000

For: VACUUM PLASMA PROCESSOR HAVING A CHAMBER WITH ELECTRODES
AND A COIL FOR PLASMA EXCITATION AND METHOD OF OPERATING
SAME

Group Art Unit: 1763

Examiner: L. Alejandro

AMENDMENT

Assistant Commissioner for Patents
Washington, D. C. 20231

Sir:

RECEIVED

OCT 07 2007

TC 1700

In response to the June 27, 2002 Office Action, please amend the application as follows:

IN THE CLAIMS:

Please amend claims 7, 8, 29, 30 and 31 as follows:

7. (amended) The vacuum plasma processor of claim 3 wherein the dielectric window, semiconductor member and non-magnetic metal arrangement are in a roof structure of the chamber, the chamber having a center portion, the coil having an interior portion that is spaced from the chamber center portion so peripheral portions of the semiconductor member are not outside the coil interior portion, the non-magnetic metal arrangement having peripheral portions spaced from the chamber center portion by approximately the same